	Application No.	Applicant(s)		
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Notice of Allowability	10/730,099 Examiner	TANAKA ÉT AL. Art Unit	<u> </u>	
	D0/40/44	2040		
	DAVID VU	2818		
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in this ap i) or other appropriate communication RIGHTS. This application is subject t	pplication. If not included n will be mailed in due co	ourse. <b>THIS</b>	
1. This communication is responsive to <u>07/11/05</u> .				
2. X The allowed claim(s) is/are <u>1-19</u> .	•			
3. $\boxtimes$ The drawings filed on <u>09 December 2003</u> are accepted by	y the Examiner.			
<ul> <li>4.  Acknowledgment is made of a claim for foreign priority of a)  All b)  Some* c)  None of the:</li> <li>1.  Certified copies of the priority documents have</li> <li>2.  Certified copies of the priority documents have</li> <li>3.  Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)).</li> <li>* Certified copies not received:</li> </ul>	re been received. re been received in Application No		on from the	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONI THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a reply MENT of this application.	complying with the requ	irements	
5. A SUBSTITUTE OATH OR DECLARATION must be subr INFORMAL PATENT APPLICATION (PTO-152) which give			TICE OF	
6. CORRECTED DRAWINGS ( as "replacement sheets") mu	ıst be submitted.			
(a) ☐ including changes required by the Notice of Draftsper	rson's Patent Drawing Review ( PTO	-948) attached		
1) ☐ hereto or 2) ☐ to Paper No./Mail Date	<u> -</u>			
(b) ☐ including changes required by the attached Examiner Paper No./Mail Date	r's Amendment / Comment or in the o	Office action of		
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in			ack) of	
7. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT.			te the	
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. X Interview Summary	<ul> <li>5. ☐ Notice of Informal Patent Application (PTO-152)</li> <li>6. ☐ Interview Summary (PTO-413), Paper No./Mail Date 20050827.</li> </ul>		
3. Information Disclosure Statements (PTO-1449 or PTO/SB/Paper No./Mail Date 12/09/03		7. Examiner's Amendment/Comment		
Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. ⊠ Examiner's Statem 9. □ Other	ent of Reasons for Allow  fuland  David Vu  Primary Exami		

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## **DETAILED ACTION**

## **EXAMINER'S AMENDMENT**

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Attorney Eckhard H. Kuesters on 08/24/05.

The applicant has been amended as follows:

Claim 20 has been cancelled.

2. Cancel claim 20.

## Reason for allowance

- 3. Claims 1-19 are allowed.
- 4. The following is an examiner's statement of reason for allowance:

With regard to method claims 1-10, the prior art of record, either singularly or in combination, does not disclose or suggest at least the claim limitations of "implanting impurity ions in said second direction from diagonally above, with said first and second mask materials being formed on said main surface, to form first doped channel regions of a first conductive type

only in said second and fifth side surfaces among said first to sixth side surfaces" as instantly claimed and in combination with the additionally claimed method steps.

With regard to method claims 11-19, the prior art of record, either singularly or in combination, does not disclose or suggest at least the claim limitations of "implanting impurity ions in said second direction from diagonally above, with said first to third mask materials being formed on said main surface, to form first doped channel regions of a first conductive type only in said second side surface of said second and third side surfaces, only in said fifth side surface of said fourth and fifth side surfaces, and only in said eighth side surface of said eighth and ninth side surfaces" as instantly claimed and in combination with the additionally claimed method steps.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

## Conclusion

5. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

US Pat. 5,364,810 – discloses a method of fabricating a vertical field-effect transistor and a semiconductor memory device. A vertical field-effect transistor may include a graded diffusion junction. The graded diffusion junctions may also form lightly doped drain structures for the vertical transistors and may reduce hot electron device degradation of the vertical transistors. Channel lengths for planar field-effect transistors typically have channel regions that are

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dependent on lithographic methods, which are typically limited by the resolution limit of the lithographic method used.

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to David Vu whose telephone number is 571-272-1798. The examiner can normally be reached on Monday-Friday 8:00am-5:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached on 571-272-1787. The fax phone numbers for the organization where this application or proceeding is assigned is (703) 872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR, Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

David Vu

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Primary Examiner